

**Amendments to the Claims:**

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-18. (Canceled)

19. (Currently Amended) An abrasive for polishing a rock crystal, a quartz glass for a photomask, a semiconductor device or a hard disk made of glass, the abrasive comprising a sol, which includes particles dispersed in an aqueous medium, wherein:

the particles comprise as a main component crystalline cerium oxide of cubic system and as an additional component a lanthanum compound, neodymium compound or a combination thereof;

the additional component is contained in an  $X/(Ce + X)$  molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof;

the particles are present in the abrasive in an amount of 0.1 to 50 wt%;

the particles have a particle size of 50 to 150 nm;

the particles have a specific surface area of 2 to 200 m<sup>2</sup>/g; and

the abrasive has a pH of ~~3 to less than 5.3~~ to 4.6.

20. (Previously Presented) An abrasive according to claim 19, wherein the additional component is a lanthanum compound.

21. (Previously Presented) An abrasive according to claim 19, wherein the additional component is a neodymium compound.

22. (Currently Amended) An abrasive for polishing an organic film with the Chemical Mechanical Polishing method, an Inter Layer Dielectric (ILD), or a shallow trench isolation of a semiconductor device, the abrasive comprising a sol, which includes particles dispersed in an aqueous medium, wherein:

the particles comprise as a main component crystalline cerium oxide of cubic

system and as an additional component a lanthanum compound, neodymium compound or a combination thereof;

the additional component is contained in an  $X/(Ce + X)$  molar ratio of 0.005 to 0.15 in which X is lanthanum atoms, neodymium atoms or a combination thereof;

the particles are present in the abrasive in an amount of 0.1 to 50 wt%;

the particles have a particle size of 50 to 150 nm;

the particles have a specific surface area of 2 to 200 m<sup>2</sup>/g; and

the abrasive has a pH of ~~3 to less than 5.3~~ to 4.6.

23. (Currently Amended) An abrasive according to ~~claim 19~~claim 22, wherein the additional component is a lanthanum compound.

24. (Currently Amended) An abrasive according to ~~claim 19~~claim 22, wherein the additional component is a neodymium compound.

25. (Previously Presented) An abrasive according to claim 19, wherein the sol further comprises at least one selected from the group consisting of a water soluble polymer, an anionic surfactant, a nonionic surfactant and a cationic surfactant.

26. (Previously Presented) An abrasive according to claim 22, wherein the sol further comprises at least one selected from the group consisting of a water soluble polymer, an anionic surfactant, a nonionic surfactant and a cationic surfactant.

27-28. (Canceled)

29. (Previously Presented) An abrasive according to claim 19, wherein the abrasive has a pH of 3 to 4.

30. (Previously Presented) An abrasive according to claim 22, wherein the abrasive has a pH of 3 to 4.